The 5th International Symposium on Advanced Plasma Processes and Diagnostics & The 1st International Symposium on Flexible Electronics Technology

Dates : April 6th(Fri.)-7th(Sat.)
Place : Sungkyunkwan University(SKKU), Suwon, Korea

Organized by
Center for Advanced Plasma Surface Technology, SKKU
Korea Institute of Surface Engineering
Flexible Electronics Research Institute Committee
Human Resources Development for BK 21 of SKKU

Co-organized by
Plasma Nanotechnology Research Center, Nagoya University, Japan
International Center for Advanced Materials Processing, UTD, U.S.A
Materia NOVA, Belgium

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Ministry of Science and Technology, Korea
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Korea Vacuum Society
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Aichi-Nagoya Knowledge Cluster Initiative in Japan Ministry of Education, Culture, Sports, Science and Technology, Japan

Date April 6th(Fri.)
Session I : Introduction of research activity of foreign institutes

09:00-09:10 : Opening addresses
09:10-09:30 : Introduction of FERI project
09:30-09:45 : Plasma Nanotechnology Research Center, Japan
09:45-10:00 : ICAMP, U.S.A.
10:00-10:15 : Materia NOVA, Belgium

10:15-10:30 : IHCE, Russia
11:30-13:30 : Ceremony of FERI

Session II : Thin film materials and processes

14:00-14:25 : Dr. Youn S. Choi, Korea
R&D to manufacturing in OLED
14:25-14:50 : Prof. Bruce Gnade, UTD, U.S.A.
Materials and Devices for Flexible Electronics
14:50-15:15 : Prof. Masaru Hori, Nagoya Univ., Japan
Advanced Plasma Cleaning and Surface Modification Technology on Flexible Materials
15:15-15:30 : Coffee break
15:30-15:55 : Prof. J. Musil, U. of West Bohemia, Czech Republic
Low Temperature Reactive Magnetron Sputtering of Oxides
15:55-16:20 : Prof. R. Snyders, Materia NOVA, Belgium
Glow discharge mass spectroscopy : a smart tool for better understanding of magnetron sputtering
16:20-16:45 : Prof. Akihiro Kono, Nagoya Univ., Japan
Properties and Diagnostics in Microwave Excited Micro Plasma
16:55-17:10 : coffee break
17:10-17:35 : Prof. D. J. Yang, UTD, U.S.A.
Transparent & conductive CNT's coating on flexible substrates and their application
17:35-18:00 : invited lecture 8 (Russia) / Dr. Nikolay Sochugov
Deposition of Al-doped zinc oxide films on polymer foil by pulsed DC reactive magnetron sputtering

18:30-21:00 : Banquet

April 7th (Sat)
09:00-09:20 : Prof. Hong Y. Chang, KAIST, Korea
Advanced plasma sources for next generation industry
09:20-09:40 : Prof. Osamu Takai
Solution Plasma Processing

09:40-10:00 : Prof. Matthew Goeckner, UTD, U.S.A.
Controlling gas chemistry in process tools for control of surface processes
10:00-10:10 : coffee break
10:10-10:30 : Prof. Nae E. Lee, SKKU, Korea
OTFT device
10:30-11:50 : Prof. Kazunori Koga and Masaharu Shiratani,
Kyushu university, Japan
Control of Deposition Profile of Cu in Trenches Using
Ion-enhanced Surface Reactions
11:50-11:10 : Prof. J. B. Lee, UTD, U.S.A.
MEMS devices on flexible substrates
11:10-11:20 : coffee break
11:20-12:20 : Student session (10 min. for each)

12:20-13:30 : Lunch

13:30-14:30 : Student session (10 min. for each)
14:30-14:50 : Prof. Jin H. Boo, SKKU, Korea
Plasma polymerization
14:50-15:10 : Prof. Yuichi Setsuhara, Osaka Univeristy, Japan
Control Capabilities of ICP Driven by Multiple Low-inductance
Antenna Modules for Low Damage Large Area Processing
- Ion Energy Distributions and Spatio-temporal Profiles -
15:10-15:30 : Prof. Jeon G. Han, SKKU, Korea
Functional metallization on polymers by hybrid plasma processing
15:30-17:30 : Poster session

18:00-21:00 : Banquet with farewell party